

ABSTRACT OF THE DISCLOSURE

An etchant includes hydrogen peroxide (H_2O_2), and a mixed solution including at least one of an organic acid, an inorganic acid, and a neutral salt.

1. A method for etching a substrate, comprising:
a. providing a substrate;
b. providing an etchant comprising hydrogen peroxide (H_2O_2), and a mixed solution including at least one of an organic acid, an inorganic acid, and a neutral salt;
c. etching the substrate with the etchant.